

Advanced Packaging

Enabling the Future of Moore's Law

Pooya Tadayon

Intel Fellow, Director of Assembly & Test Pathfinding

intel®

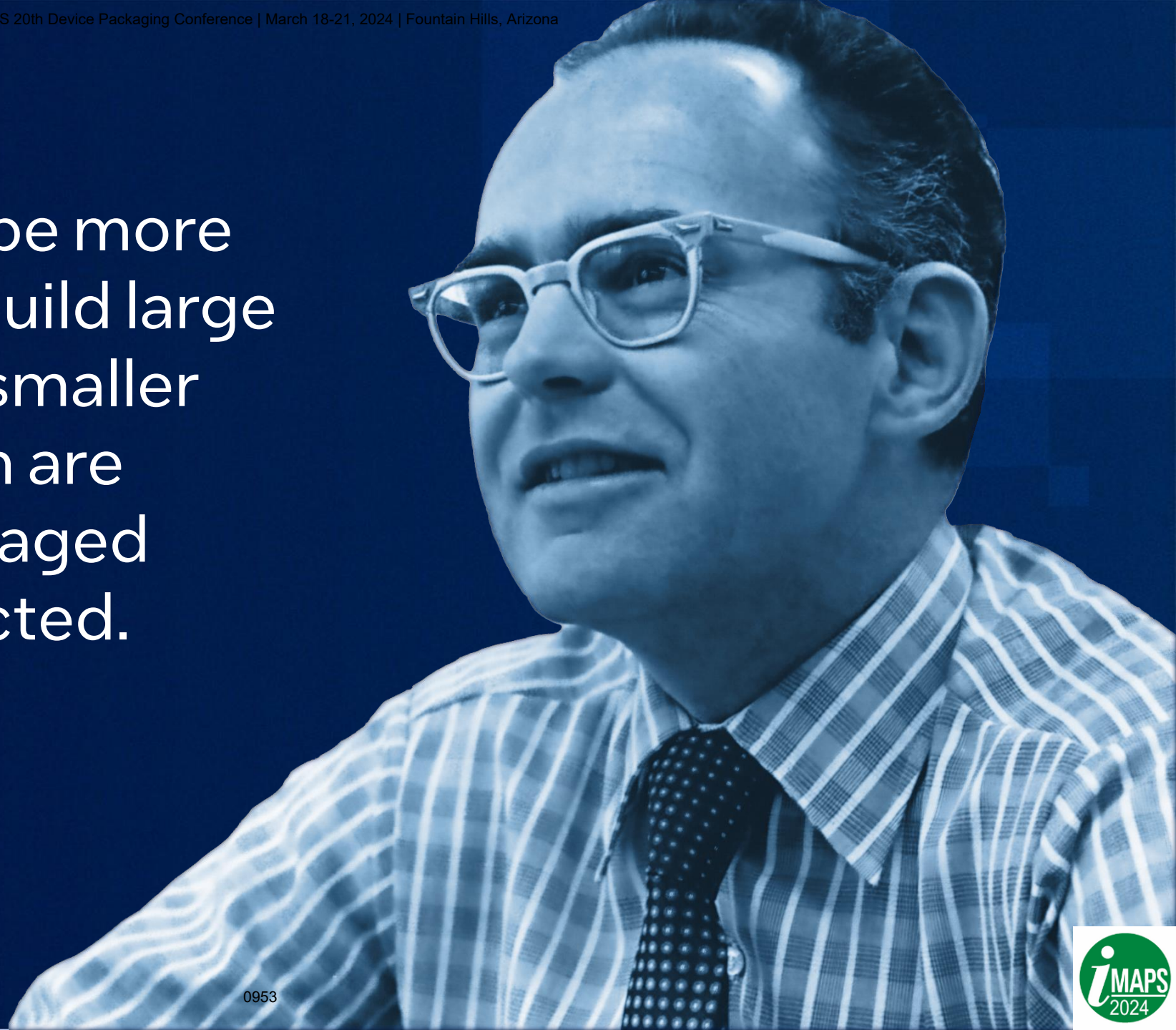
Executive Summary

- Industry is trending towards more complex integration schemes to address cost and scalability challenges
- The era of 3D integration and advanced packaging is upon us, but the ecosystem is not ready
 - There are fundamental design, manufacturing, and enabling challenges that must be addressed
- Metrology, physical debug, and manufacturing test are underserved and need more focus and investment from industry and academic partners
 - “if you can’t test it, you don’t have a product”

It may prove to be more economical to build large systems out of smaller functions, which are separately packaged and interconnected.

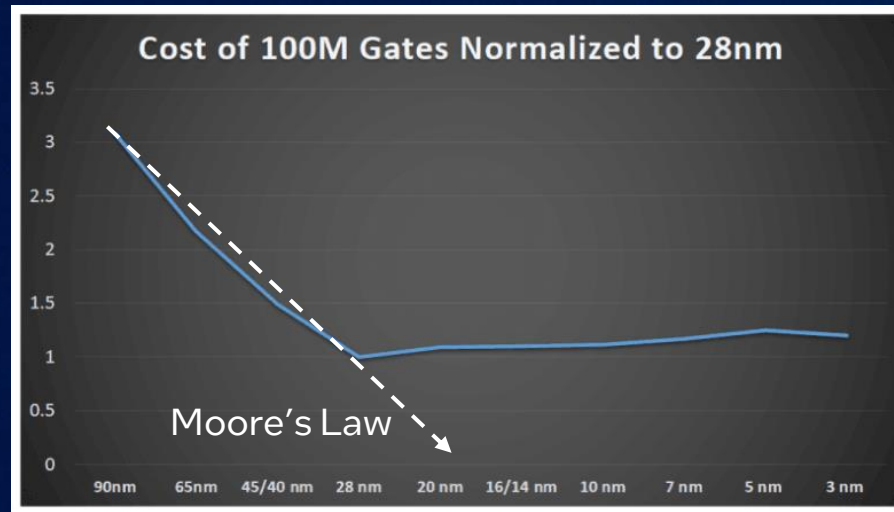
Gordon Moore
Electronics, 1965

Image credit - betanews



Technology Drivers

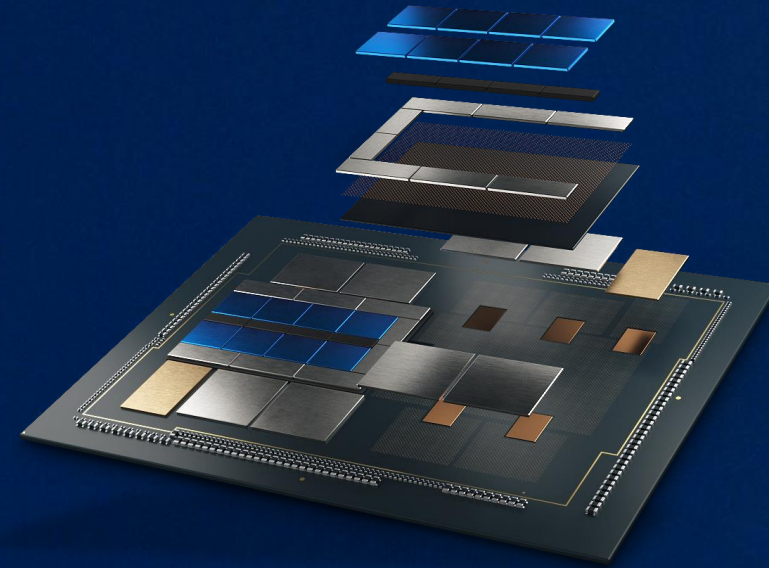
COST



Source: Google, IEDM23, SC1.6

Higher wafer cost drives
disaggregation

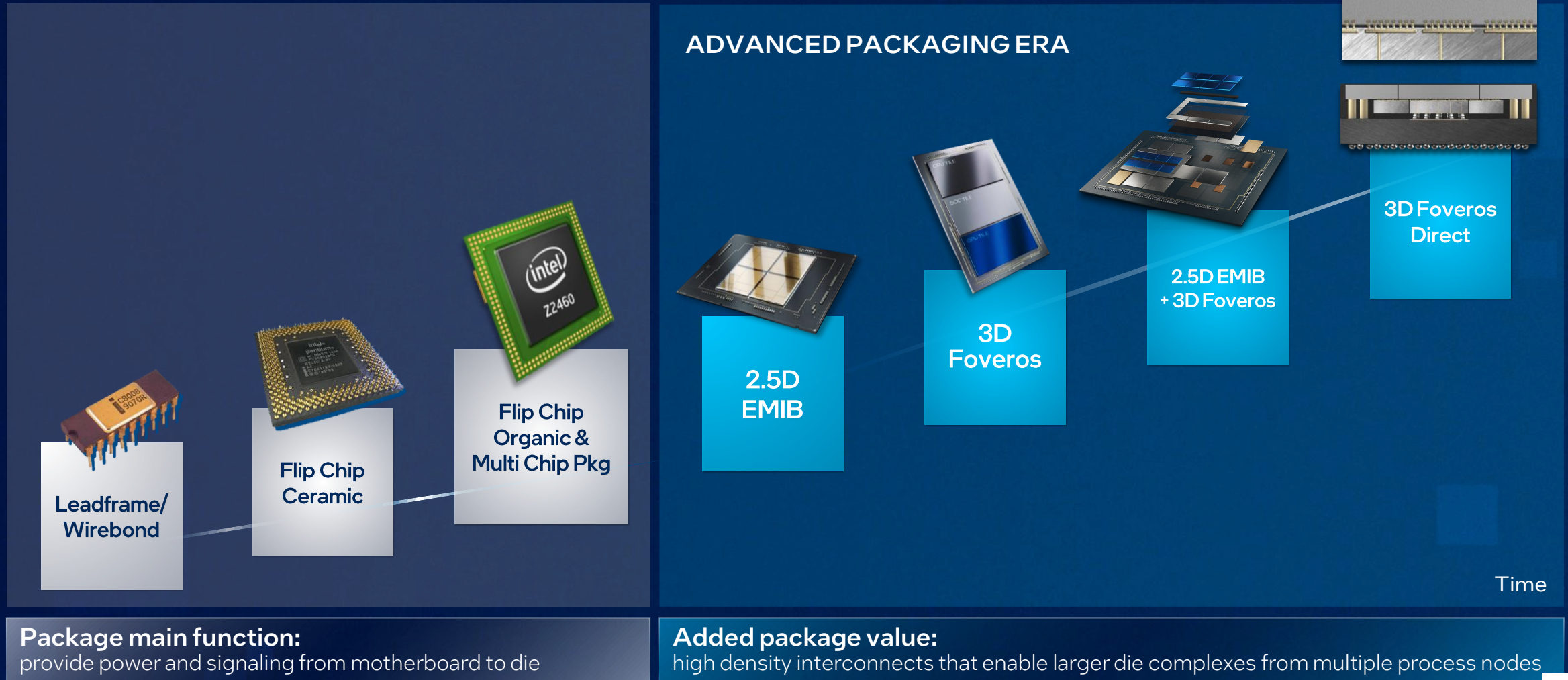
PERFORMANCE/SCALING



Need for complex sizes that
exceed the reticle limit

Advanced packaging is required to re-aggregate chiplets and build complexes larger than the reticle limit

Evolution of Advanced Packaging



Evolution of 3D Packaging



3D today
"planar"

3D future
"cube"

3D stacking will evolve to enable more complex and integrated devices

Key Challenges: Power Delivery & Thermals

"low-power memory on top of high-power logic"



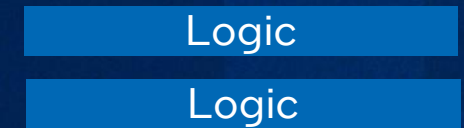
+Direct power delivery to logic die
-High-power logic die is thermally blocked

"high-power logic on top of low-power memory"



-Degraded power delivery to logic die
+Direct thermal access to high-power logic die

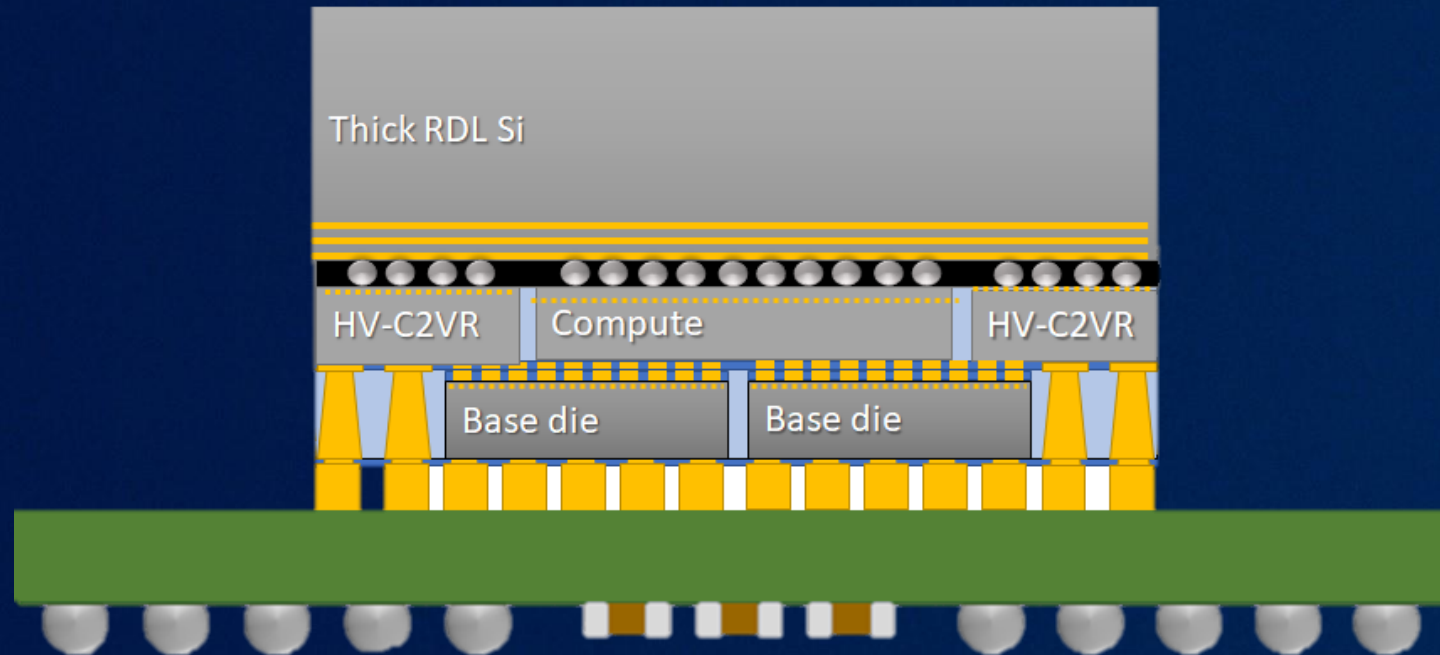
"high-power logic on top of high-power logic"



-Degraded power delivery to top die
-High-power bottom die is thermally blocked

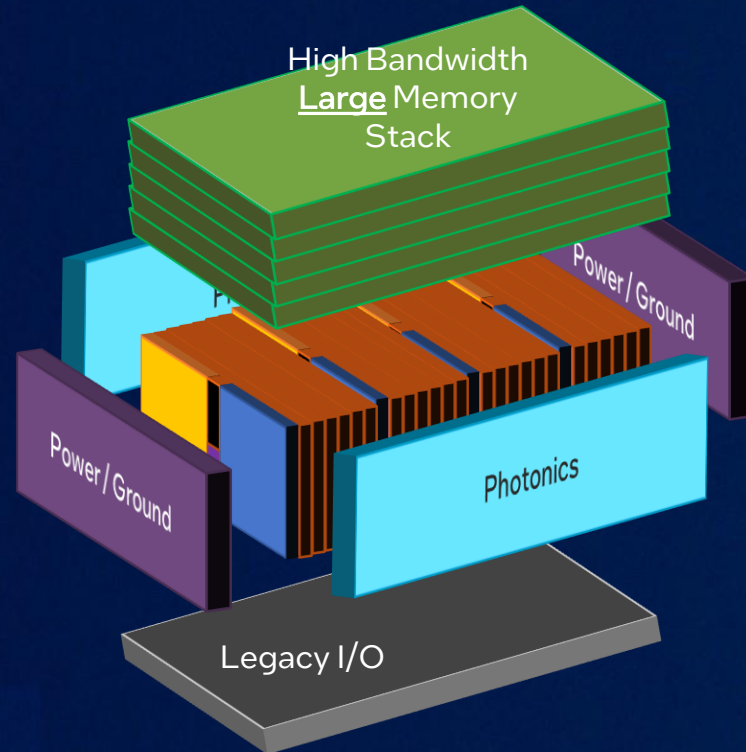
Innovations needed in power delivery and thermals to extract maximum value out of 3D stacking

Key Challenges: Power Delivery & Thermals



Topside power delivery may be a solution path, but adds cost and complexity

Key Challenges: Process & Design



Manufacturing:

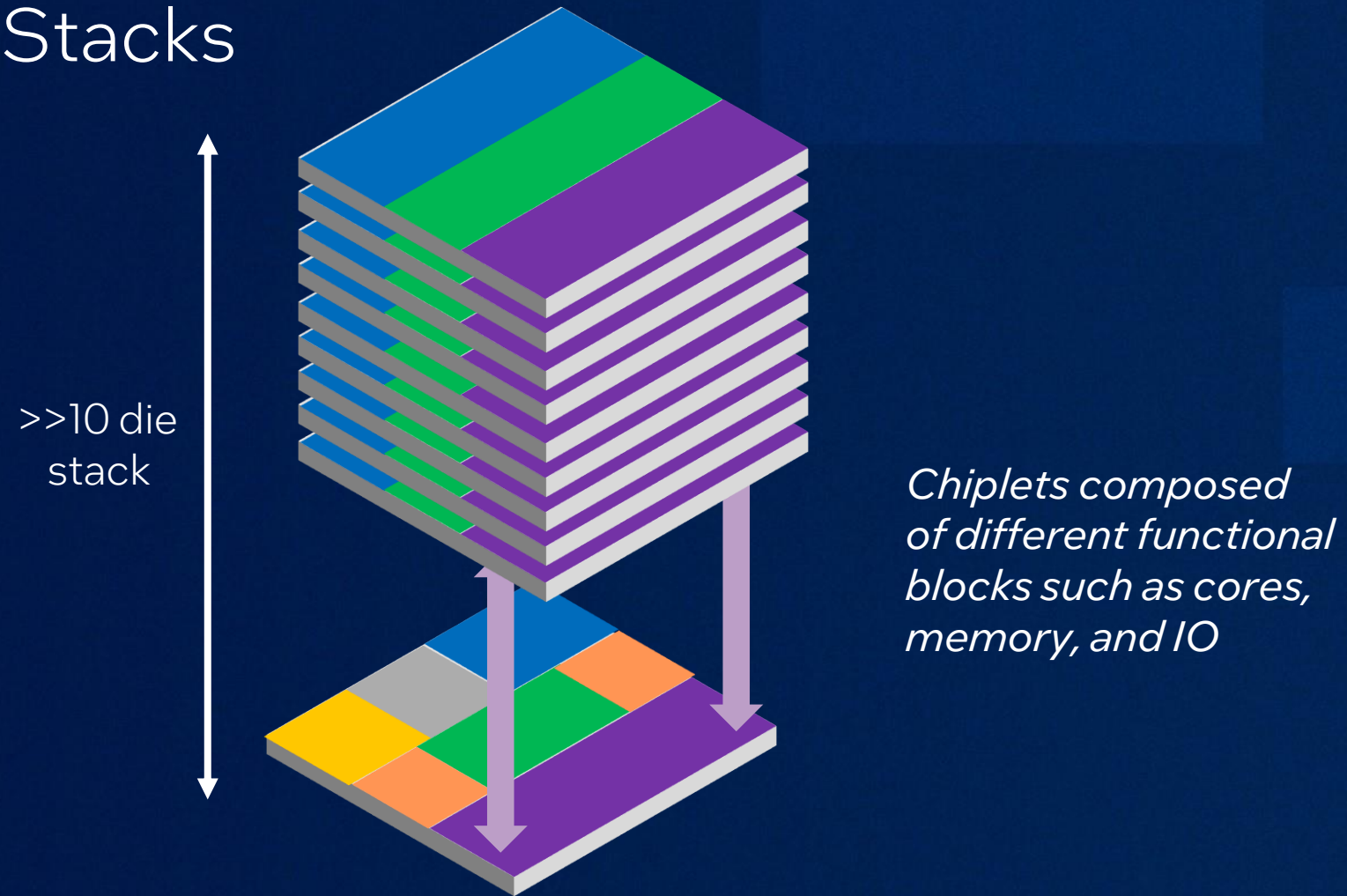
- Die/stack rotation
- Edge polish & attach
- Z-height
- Physical debug

Design:

- Die rotation & die edge egress
- Non-planar libraries
- Power delivery & thermals

New manufacturing tools & processes along with new design tools and methodologies are needed to enable “cube” architectures

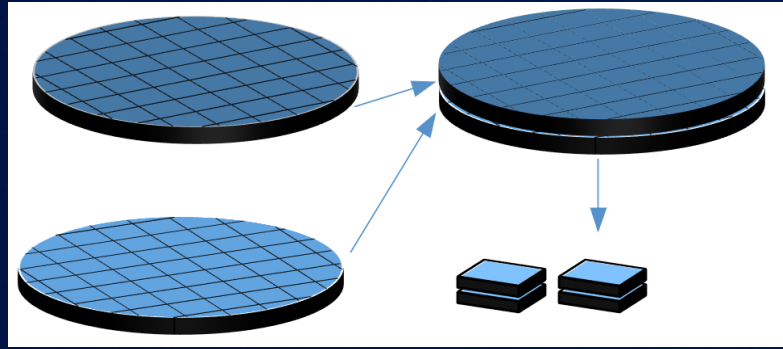
Trends: Super Stacks



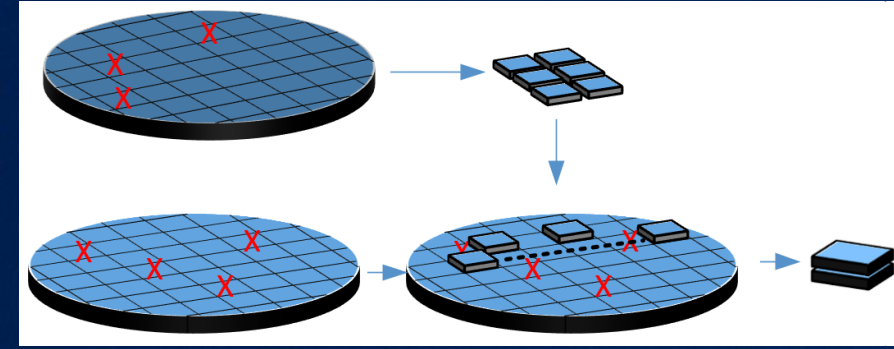
Super Stacks being proposed as a path to achieve best-in-class size, weight, power, and cost

Key Challenges: Super Stacks

Wafer-to-Wafer (W2W)



Chip-to-Wafer (C2W)



More mature, faster throughput

Currently finer pitch

Stacked die must be the same size

Random pairing of die

Cumulative yield issue (all die must work)

Less mature, slower throughput

Currently coarser pitch with roadmap to finer pitch

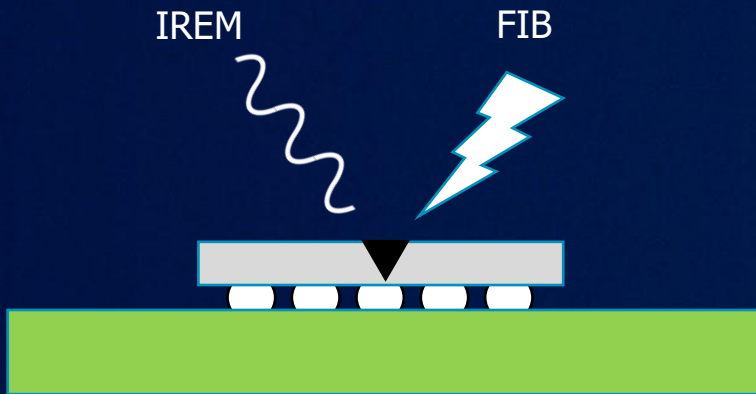
No limitations on stacked die relative sizes

Intelligent pairing of die

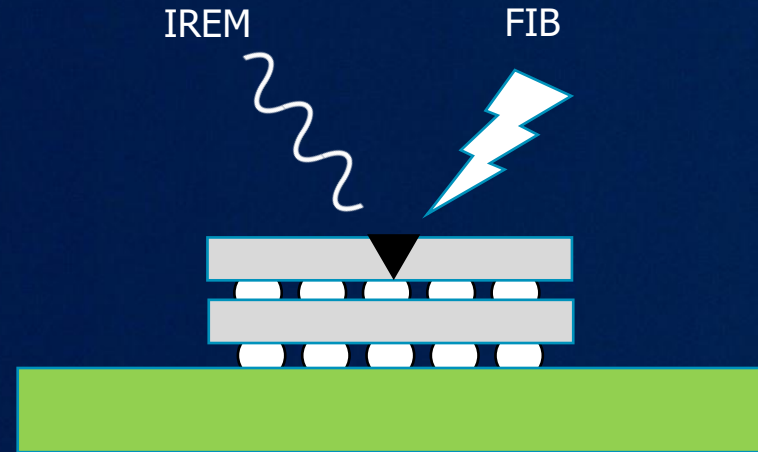
No cumulative yield (all die are tested before attach)

New tools and flows needed to enable economically viable Super Stacks

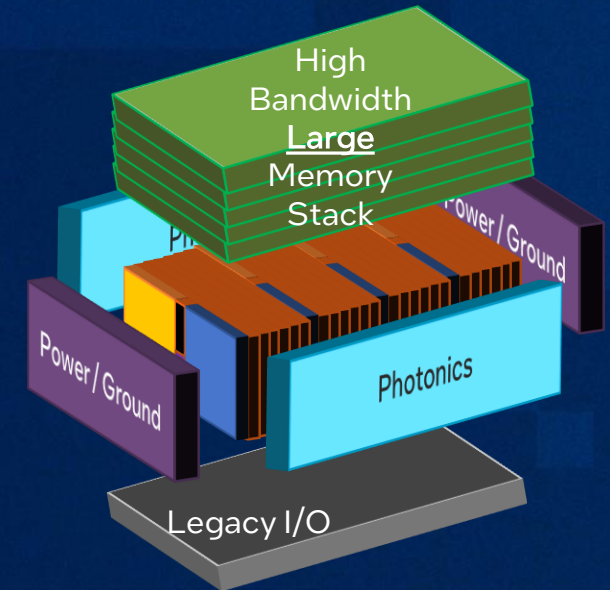
Key Challenges: Physical Debug



All transistors are accessible



Bottom die transistors are blocked by the top die and are inaccessible

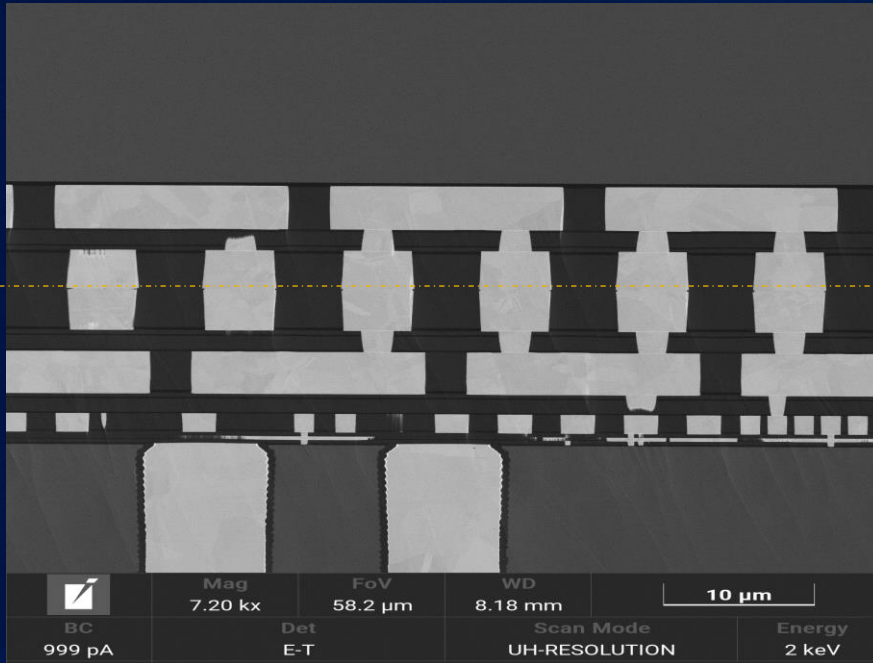


???

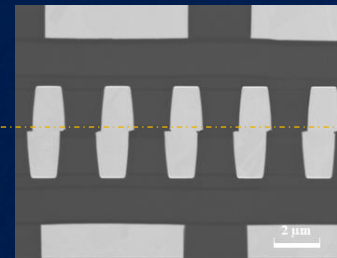
Need new physical debug techniques to enable more complex stacking strategies

Trends: Pitch Scaling

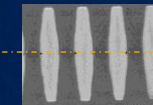
9 um pitch



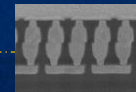
3 um pitch



1 um pitch



0.4 um pitch

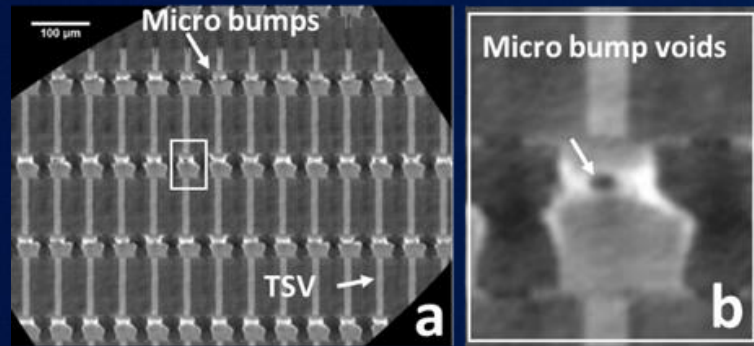


time

Cu-Cu hybrid bonding enables aggressive pitch scaling to ≤ 1 um

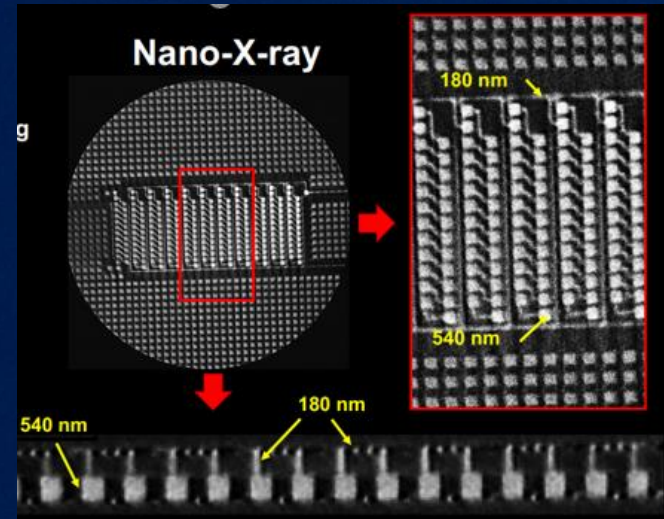
Key Challenges: Defect Detection

Typical 3D X-ray for interconnect defects; no sample prep is needed



Cheryl Hartfield et. al. DOI: 10.1109/IPFA.2018.8452551

Nano 3D X-ray with $<1\mu\text{m}$ res.; sample preparation is needed

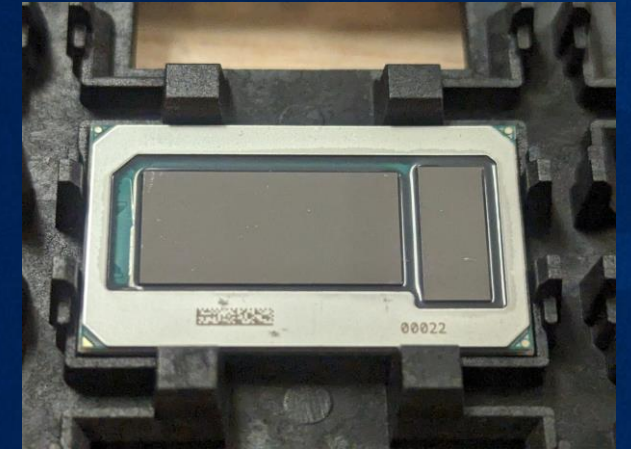
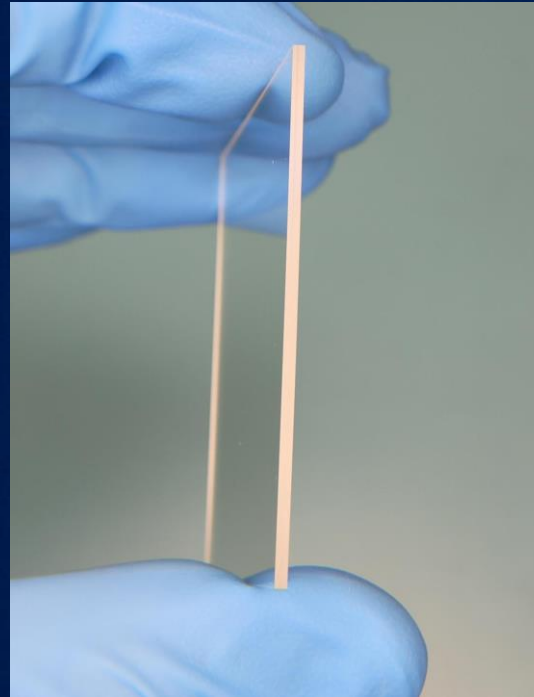
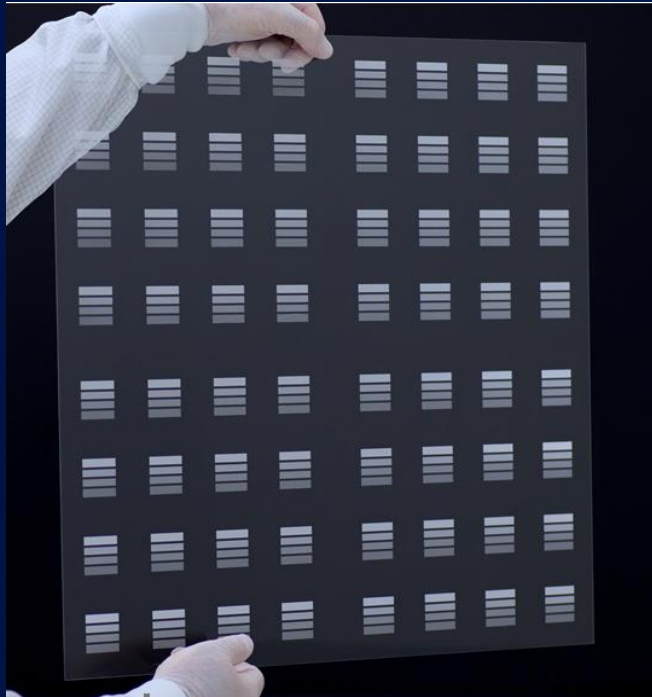


Christian Schmidt, Lorenz Lechner, Ingrid DeWolf, Soon-Wook Kim, Eric Beyn ECTC 2018

Sample prep and long scanning time needed to reach high resolution for fine pitch features will slow down yield learnings and impact time to market

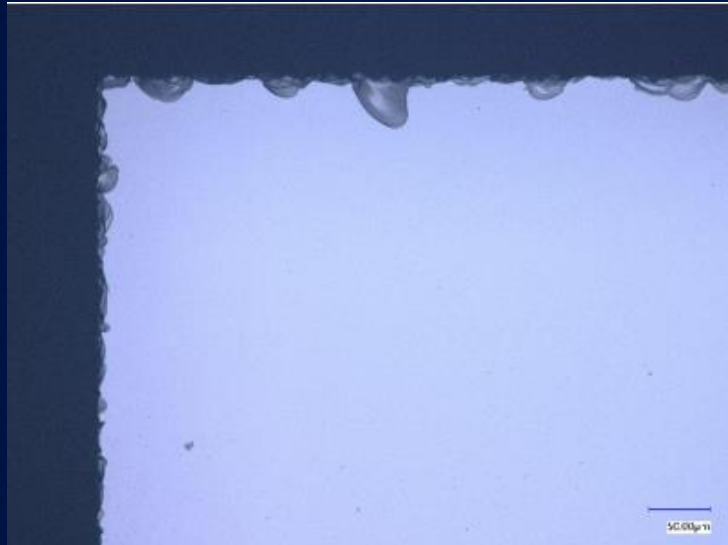
Need innovations in imaging and FA methods to quickly and non-destructively catch sub-micron defects buried under multiple interfaces

Trends: Glass Substrates



Glass offers improved material properties resulting in better dimensional stability and ability to scale

Key Challenges: Process & Metrology



Edge defects due to singulation



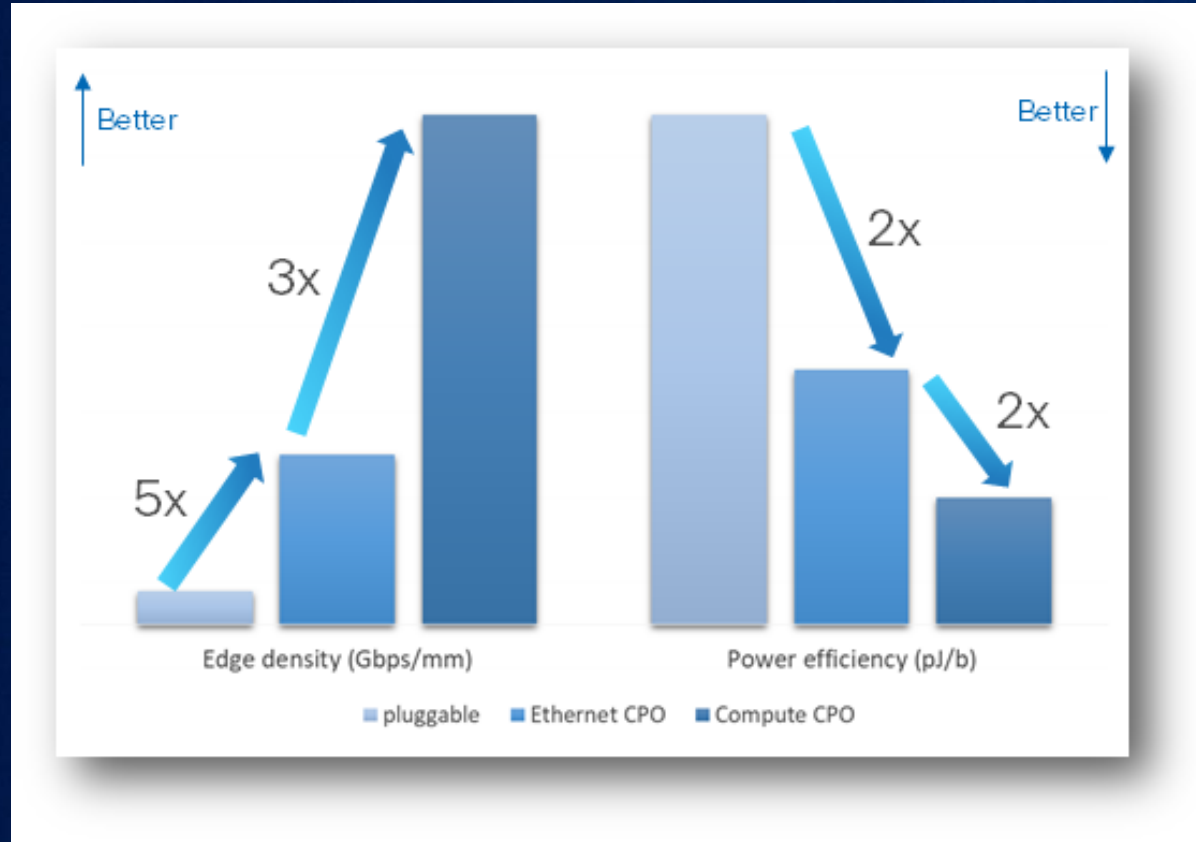
Corner chipping due to material handling



Cracks that can become gross fails if undetected

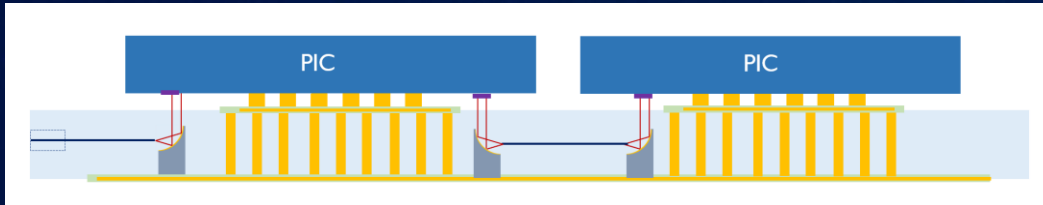
New processing techniques, material handling, and in-line metrologies required to enable manufacturing of glass substrates

Trends: Co-Packaged Optics



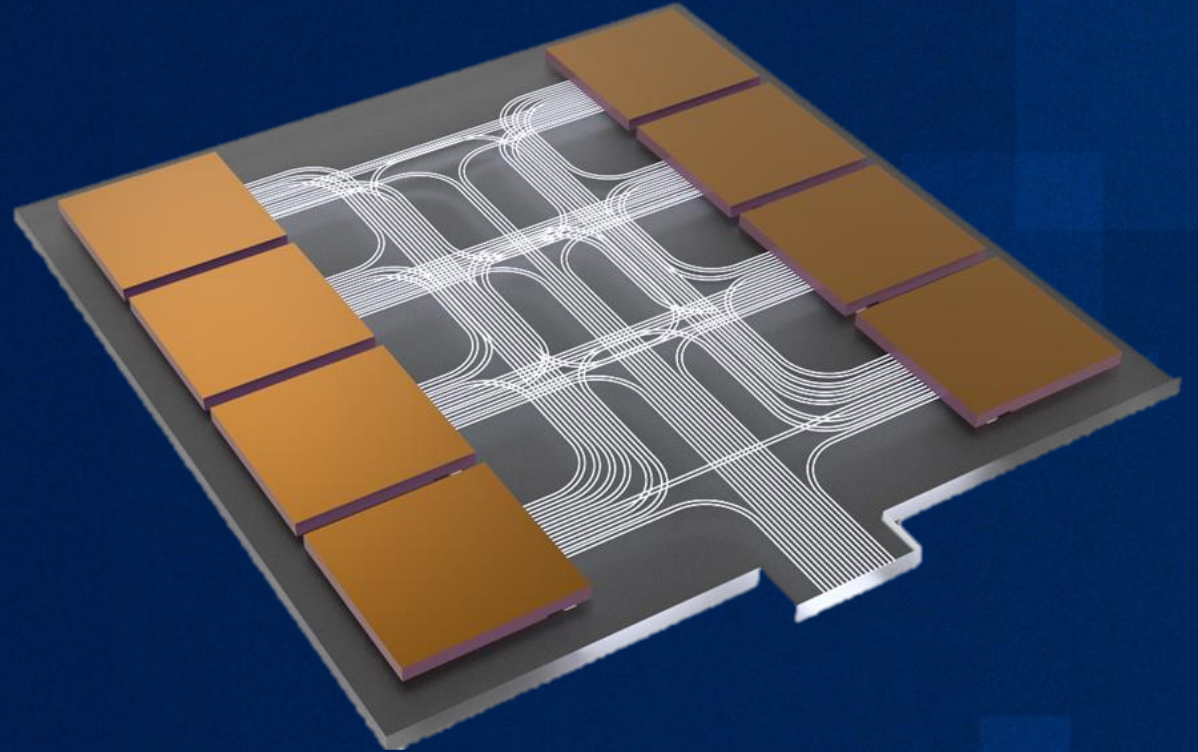
Co-packaged Optics will grow bandwidth/socket and improve IO power efficiency

Key Challenges: Optical Integration in Glass Substrates



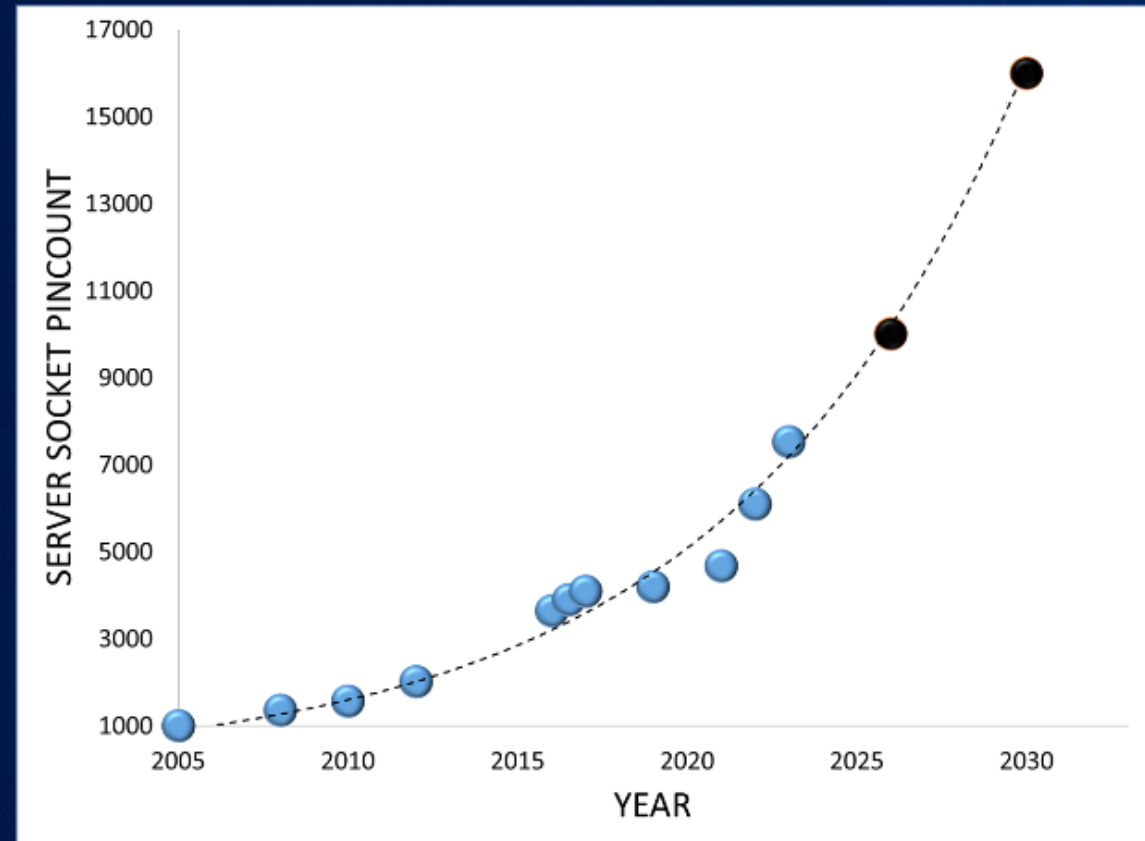
Key building blocks:

- *Lower propagation loss waveguides*
- *Programmable waveguide mesh*
- *EDA tool for electrical/optical design*
- *Faster waveguide writing*
- *Better/faster waveguide metrology*



Full optical integration in glass substrates for chip-to-chip communication in large-scale systems

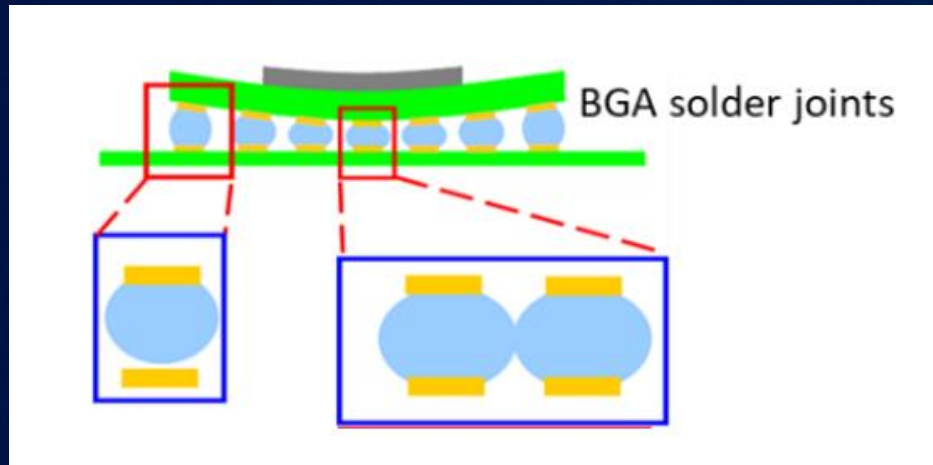
Trends: Larger Substrates with Higher Pincounts



Larger complexes drive larger packages which leads to an exponential increase in pincount

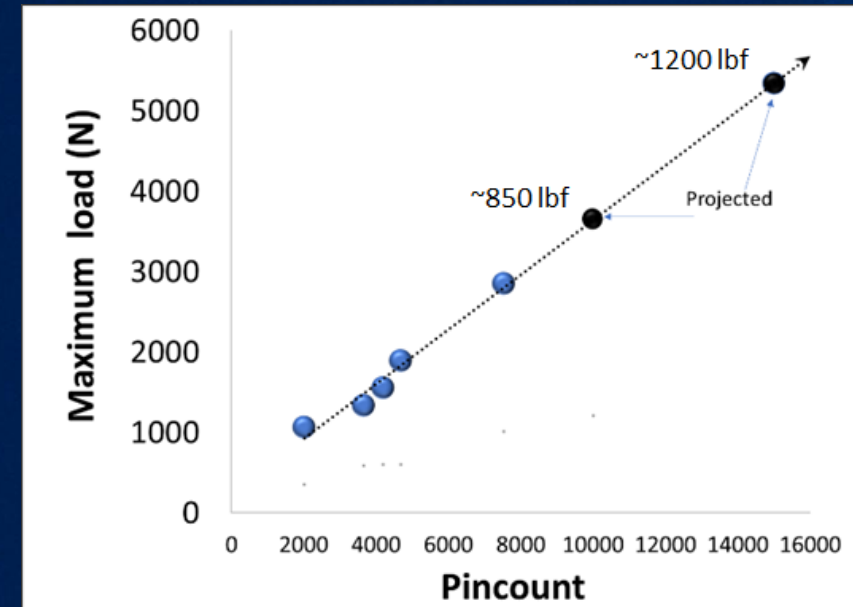
Challenges: Board Attach

Ball Grid Array (BGA)



Larger packages result in higher warpage which lead to a less reliable surface mount process

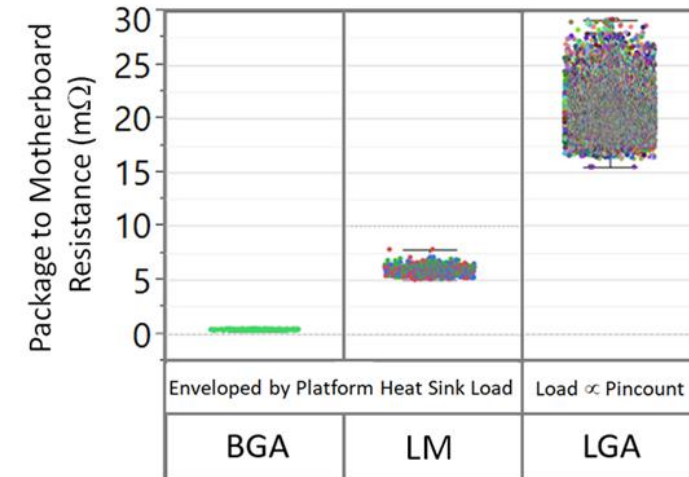
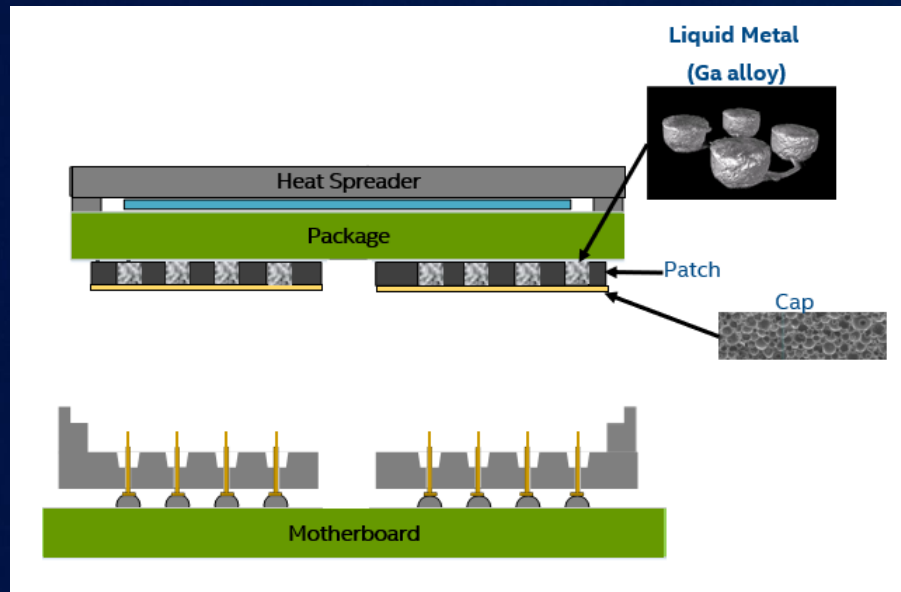
Land Grid Array (LGA)



As pin count grows, the total sustained load required by the socket grows linearly

Larger packages with higher pincount challenge both BGA and LGA solutions

Challenges: Board Attach



Electrical performance	✓	✓	✗
Loading mechanism complexity & cost	✓	✓	✗
Late attach/separable	✗	✓	✓

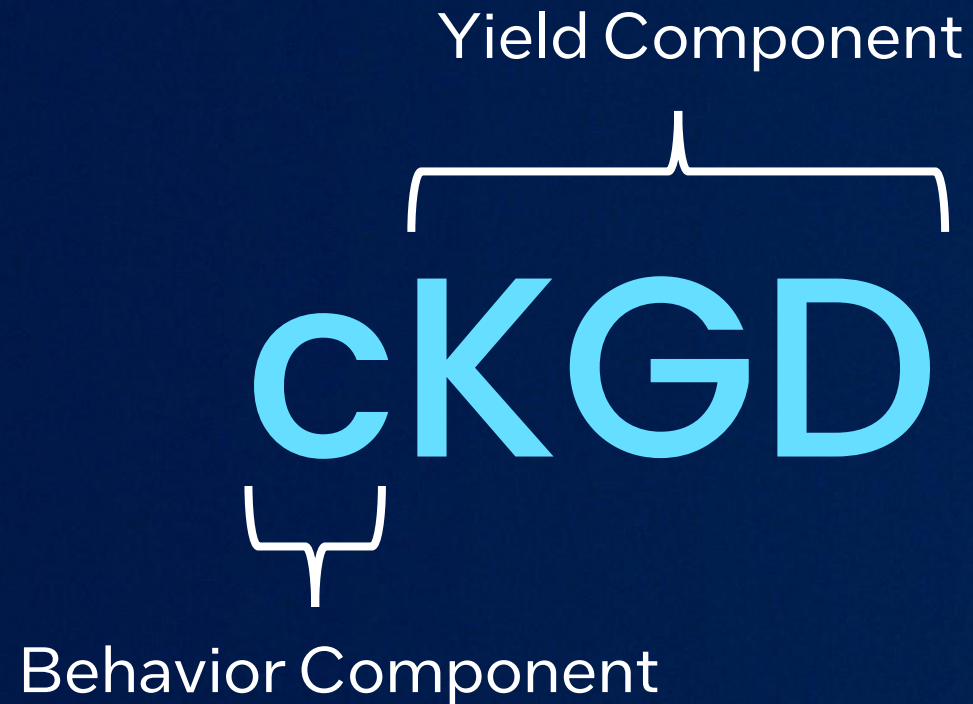
Liquid metal (LM) offers a ~zero load interconnect that has the goodness of BGA and the flexibility of LGA, but requires significant ecosystem maturation

Key Challenges: Test



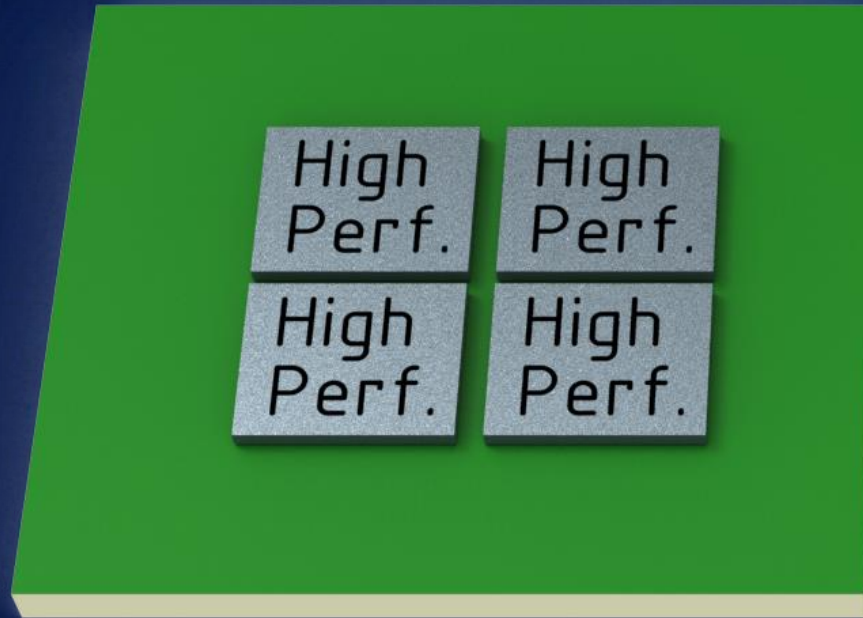
Characterized Known-Good-Die (cKGD) out of wafer test is critical to making 3DIC economically viable

What is cKGD?



Wafer test needs to not only catch defects, but also provide an accurate assessment of device behavior for optimal die pairing decisions

Importance of Characterization



Shipped as high performing part



Shipped as medium performing part

Characterization of device behavior/performance and intelligent pairing is needed to maximize performance

cKGD Challenges

Silent Data Corruptions at Scale 

Harish Dattatraya
Dixit
Facebook, Inc.
hdd@fb.com

Sneha Pendharkar
Facebook, Inc.
spendharkar@fb.com

Matt Beadon
Facebook, Inc.
mbeadon@fb.com

Chris Mason
Facebook, Inc.
clm@fb.com

Tejasvi Chakravarthy
Facebook, Inc.
teju@fb.com

Bharath Muthiah
Facebook, Inc.
bharathm@fb.com

Sriram Sankar
Facebook Inc.
sriramsankar@fb.com

ABSTRACT
Silent Data Corruption (SDC) can have negative impact on large-scale infrastructure services. SDCs are not captured by error reporting mechanisms within a Central Processing Unit (CPU) and hence are not traceable at the hardware level. However, the data corruptions propagate across the stack and manifest as application-level problems. These types of errors can result in data loss and can require months of debug engineering time.
In this paper, we describe common defect types observed in silicon manufacturing that leads to SDCs. We discuss a real-world

machine learning inferences, ranking and recommendation systems. However, it is our observation that computations are not always accurate. In some cases, the CPU can perform computations incorrectly. For example, when you perform 2x3, the CPU may give a result of 5 instead of 6 silently under certain microarchitectural conditions, without an indication of the miscomputation in system event or error logs. As a result, a service utilizing the CPU is potentially unaware of the computational accuracy and keeps consuming the incorrect values in the application. This paper predominantly focuses on scenarios where datacenter CPUs exhibit such silent data

Cores that don't count 

Peter H. Hochschild
Paul Turner
Jeffrey C. Mogul
Google
Sunnyvale, CA, US

Rama Govindaraju
Parthasarathy
Ranganathan
Google
Sunnyvale, CA, US

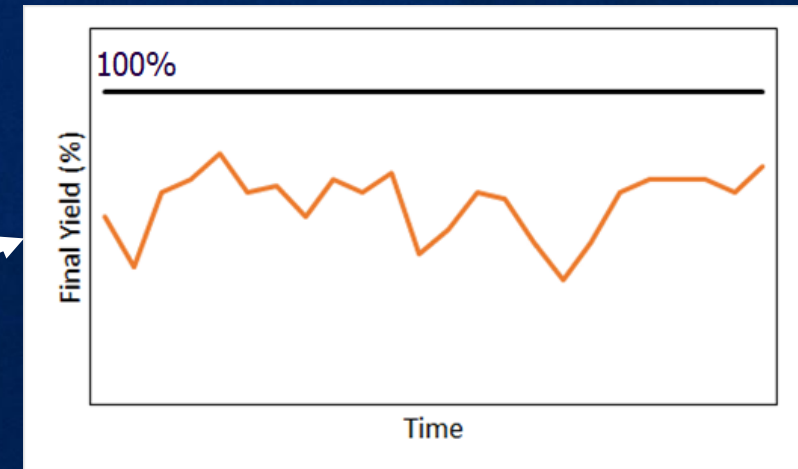
David E. Culler
Amin Vahdat
Google
Sunnyvale, CA, US

Abstract
We are accustomed to thinking of computers as fail-stop, especially the cores that execute instructions, and most system software implicitly relies on that assumption. During most of the VLSI era, processors that passed manufacturing tests and were operated within specifications have insulated us from this fiction. As fabrication pushes towards smaller feature sizes and more elaborate computational structures, and as increasingly specialized instruction-silicon pairings are introduced, the risk of silent data corruption (SDC) increases. In this paper, we describe common defect types observed in silicon manufacturing that leads to SDCs. We discuss a real-world

1 Introduction
Imagine you are running a massive-scale data-analysis pipeline in production, and one day it starts to give you wrong answers – somewhere in the pipeline, a class of computations are yielding corrupt results. Investigation fingers a surprising cause: an innocuous change to a low-level library. The change itself was

MI, USA. ACM, New York, NY, USA, 8 pages. <https://doi.org/10.1145/3458336.3465297>

cKGD



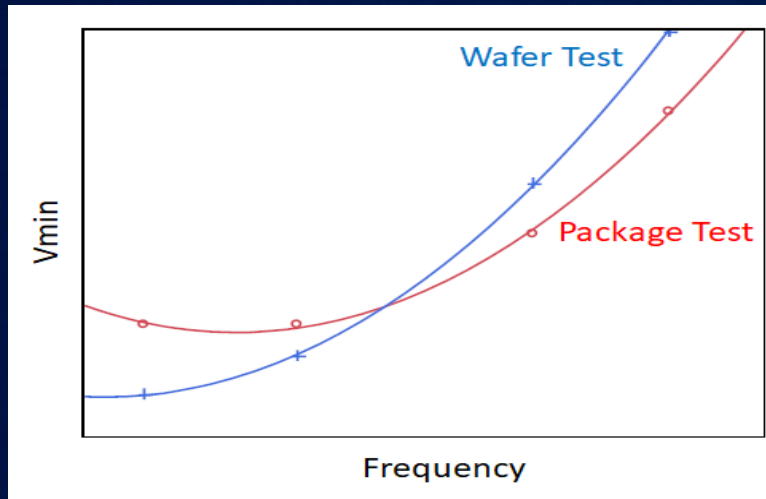
Despite best efforts to produce KGD out of wafer test, there are still a significant number of defects that are being caught at package test

Even package level test has challenges catching all defects due to differences in the test vs use environment

Defects are getting harder to catch and test methods and strategies are not keeping pace

cKGD Challenges

	Wafer Test	Package Test
Thermal	Cold/warm, passive cooling	Hot, active cooling
Electrical	No package, limited connectivity	Package, full connectivity
Mechanical	No package, flat die	Package, warped die

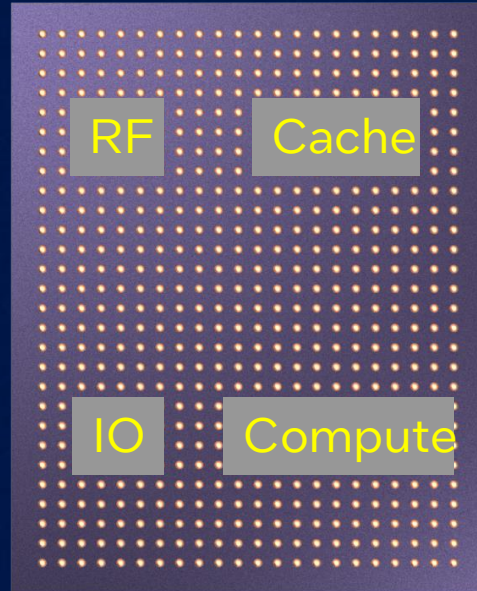


cKGD

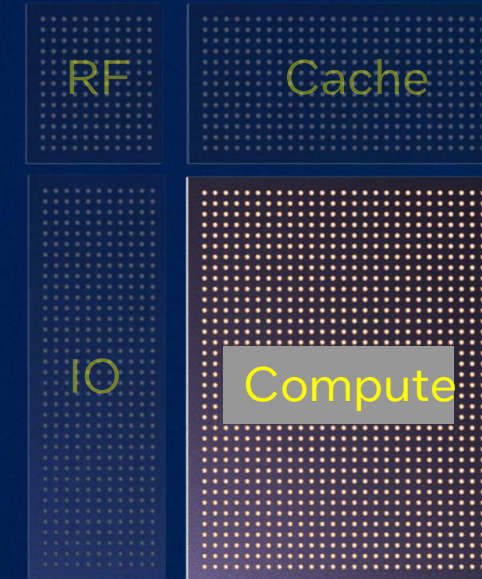
Device performance shifts due to differences in the wafer test vs backend test environment

Differences in wafer test vs backend test environment present challenges in properly characterizing chiplets

Characterization Challenges



All functional blocks are present during wafer test



Functional blocks are distributed and not present during wafer test

Need methods for effective testing and characterization of disaggregated chiplets that don't have all the functional blocks available during wafer test

Executive Summary

- Industry is trending towards more complex integration schemes to address cost and scalability challenges
- The era of 3D integration and advanced packaging is upon us, but the ecosystem is not ready
 - There are fundamental design, manufacturing, and enabling challenges that must be addressed
- Metrology, physical debug, and manufacturing test are underserved and need more focus and investment from industry and academic partners
 - “if you can’t test it, you don’t have a product”



All product and service plans, and roadmaps are subject to change without notice. Any forecasts of products, services or technologies needed for Intel's operations are provided for discussion purposes only. Intel will have no liability to make any purchase in connection with forecasts published in this document. Code names are often used by Intel to identify products, services or technologies that are in development and usage may change over time. Product, service and technology performance varies by use, configuration and other factors. No license (express or implied, by estoppel or otherwise) to any intellectual property rights is granted by this document. Learn more at www.Intel.com/PerformanceIndex and www.Intel.com/ProcessInnovation.

Reference to research results, including comparisons to products, services or technology performance are estimates and do not imply availability. The products and services described may contain defects or errors which may cause deviation from published specifications. Current characterized errata are available on request. Intel disclaims all express and implied warranties, including without limitation, the implied warranties of merchantability, fitness for a particular purpose, and non-infringement, as well as any warranty arising from course of performance, course of dealing, or usage in trade. Statements in this document that refer to future plans or expectations are forward-looking statements. These statements are based on current expectations and involve many risks and uncertainties that could cause actual results to differ materially from those expressed or implied in such statements. For more information on the factors that could cause actual results to differ materially, see our most recent earnings releases, annual report on form 10-K and other SEC filings at www.intc.com.

© Intel Corporation. Intel, the Intel logo, and other Intel marks are trademarks of Intel Corporation or its subsidiaries. Other names and brands may be claimed as the property of others. This document contains information on products and technologies in development.